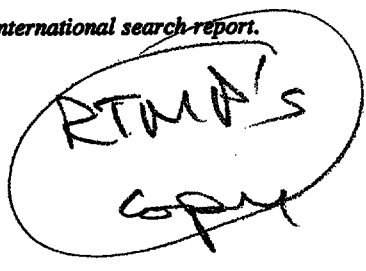


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| <b>(21) International Application Number:</b> PCT/US95/02331<br><b>(22) International Filing Date:</b> 24 February 1995 (24.02.95)<br><b>(30) Priority Data:</b><br>08/208,546 9 March 1994 (09.03.94) US<br><b>(71) Applicant:</b> W.R. GRACE & CO.-CONN. [US/US]; 1114 Avenue of the Americas, New York, NY 10036 (US).<br><b>(72) Inventors:</b> HALLOCK, John, Scott; 10324 Kingsbridge Road, Ellicott City, MD 21042 (US). BECKNELL, Allan, Frederick; 8549 Trail View Drive, Ellicott City, MD 21043 (US). EBNER, Cynthia, Louise; 6235 Sawyer Road, New Market, MD 21774 (US). HART, Daniel, Joseph; 2997 Patapsco Road, Finksburg, MD 21048 (US).<br><b>(74) Agent:</b> GANDHI, Bharat, C.; W.R. Grace & Co.-Conn., 7379 Route 32, Columbia, MD 21044 (US).                                                                                                      |           | <b>(81) Designated States:</b> AM, AT, AU, BB, BG, BR, BY, CA, CH, CN, CZ, DE, DK, EE, ES, FI, GB, GE, HU, JP, KE, KG, KP, KR, KZ, LK, LR, LT, LU, LV, MD, MG, MN, MW, MX, NL, NO, NZ, PL, PT, RO, RU, SD, SE, SG, SI, SK, TJ, TT, UA, UG, UZ, VN, European patent (AT, BE, CH, DE, DK, ES, FR, GB, GR, IE, IT, LU, MC, NL, PT, SE), OAPI patent (BF, BJ, CF, CG, CI, CM, GA, GN, ML, MR, NE, SN, TD, TG), ARIPO patent (KE, MW, SD, SZ, UG).<br><br><b>Published</b><br><i>With international search report.</i><br><br> |
| <b>(54) Title:</b> STABLE, IONOMERIC PHOTORESIST EMULSION AND PROCESS OF PREPARATION AND USE THEREOF<br><br><b>(57) Abstract</b><br><br>Disclosed are waterborne, stable photoresist compositions and methods of their preparation and use. The compositions are characterized by increased shear and storage stability. The photoresist composition comprises an aqueous emulsion of a 22 % or less neutralized carboxylated resin and non-ionic surfactant containing poly(ethylene-oxide) segments, photopolymerizable monomer and photoinitiator. Neutralization is accomplished using either an organic or an inorganic base or mixtures thereof. The photoresist compositions are useful to selectively coat and protect surfaces subjected to corrosive environments, e.g., etchant processes, in the production of circuit traces for electronic circuit boards. |           |                                                                                                                                                                                                                                                                                                                                                                                                                                                                                                                                                                                                             |

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